

Form PTO 1449
(Modified)DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY DOCKET NO.
239720US90CONTSERIAL NO.
10/608,032

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT
Toshio TSUKAKOSHIFILING DATE
June 30, 2003GROUP
2877

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
MD	AA	6,078,554	06/20/2000	OOTAKI, et al.			
MD	AB	6,118,535	09/12/2000	GOLDBERG, et al.			
MD	AC	6,100,978	08/08/2000	NAULLEAU, et al.			
MD	AD	2002/0001071 A1	01/03/2002	NOMURA, et al.			
MD	AE	5,754,299	05/19/1998	SUGAYA, et al.			
MD	AF	6,329,112	12/11/2001	FUKUDA, et al.			
MD	AG	5,807,647	09/15/1998	HASHIMOTO			
MD	AH	5,321,493	06/14/1994	KAMON			
MD	AI	4,786,166	11/22/1988	KROKO			
MD	AJ	5,898,501	04/27/1999	SUZUKI, et al.			
MD	AK	6,245,470	06/12/2001	KAMON			
MD	AL	6,268,903	07/31/2001	CHIBA, et al.			
MD	AM	6,459,480	10/01/2002	KYE			
MD	AN	6,570,143	05/27/2003	NEIL, et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
MD	AO	198 20 785.9 A1	10/21/1999	Germany		x
MD	AP	2000-146757	05/26/2000	Japan (w/ English abstract and machine translation)	x	
MD	AQ	2000-266640	09/29/2000	Japan (w/ English abstract and machine translation)	x	
MD	AR	WO 00/55890	09/21/2000	WIPO (w/ English abstract)		x
MD	AS	2001-230193	08/24/2001	Japan (w/ English abstract and machine translation)	x	
MD	AT	1 355 140 A1	10/22/2003	Europe (corresponding to U.S. Application 10/608,032)		
MD	AU	1 359 608 A1	11/05/2003	Europe		
MD	AV	WO 02/50506 A1	06/27/2002	WIPO (w/ English abstract)		x
MD	AW	0 267 721	05/18/1988	Europe		
MD	AX	0 338 200	10/25/1989	Europe		
	AZ					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

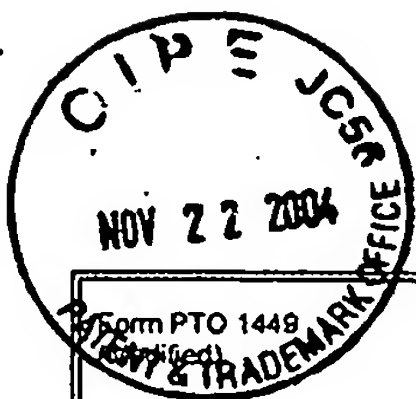
MD	BA	Winter 1998 MICROLITHOGRAPHY WORLD pages 11-20 Authors: Donis G. Flagello and Bernd Geh Title: "The influence of lens aberrations in lithography"
MD	BB	Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, US, vol. 16, no. 6, November 1998 (1998-11) pages 3435-3439 Authors: K. Goldberg, et al. Title: "High-accuracy interferometry of extreme ultraviolet lithographic optical system"
	BC	<input type="checkbox"/> Additional References sheet(s) attached

Examiner

Date Considered

3/8/05

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



LIST OF REFERENCES CITED BY APPLICANT		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 239720US90CONT		SERIAL NO. 10/608,032	
		APPLICANT Toshio TSUKAKOSHI					
		FILING DATE June 30, 2003		GROUP 2877			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
20	AA	6,741,327	05/25/2004	Nomura, et al.	—	—	
	AB						
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	AW						
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	AZ					<input type="checkbox"/> Additional References sheet(s) attached	
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